

### e-GGRT Training Webinar

Reporting of GHG Data for Subpart I – RY 2014 Electronics Manufacturing

U.S. Environmental Protection Agency
Greenhouse Gas Reporting Program (GHGRP)



This training is provided by EPA solely for informational purposes. It does not provide legal advice, have legally binding effect, or expressly or implicitly create, expand, or limit any legal rights, obligations, responsibilities, expectations, or benefits in regard to any person.

### Webinar Overview



### Subpart I Reporting

- Background on rule changes
- Change from Excel form to Web form
- How to access/add a Subpart I module to your e-GGRT account
- Entering Data into the Subpart I Web form
- Generating, certifying, and submitting reports
- Where to get help

## Not covered in Today's Webinar



- How to register a new facility
- How to manage an account (e.g., editing facility profiles, appointing DRs/ADRs)
- How to register new agents
- How to report GHG emissions for other applicable subparts (e.g., subpart C)

For help with these and other topics, see the e-GGRT Help Site at <a href="http://www.ccdsupport.com">http://www.ccdsupport.com</a>

## Topics for Today's Q & A



- During the webinar, please submit only questions regarding how to use e-GGRT to report GHG emissions under Subpart I.
- Questions on other topics (requirements of the Greenhouse Gas Reporting Rule, legal issues, etc.) should be submitted to GHGReporting@epa.gov

## Background & Rule Changes for 2014



- E-GGRT reflects the calculation methods, reporting, and recordkeeping requirements from the 2013 subpart I rule amendments (77 FR 68162, published November 13, 2013)
  - Revised methods for calculating GHG emissions
  - Revised reported data elements
- Final rule amendments became effective for all reporters on January 1, 2014.
  - Calculations for RY 2014 should reflect rule changes
  - Do <u>not</u> use the previous version of the Calculation Tool for RY 2014
  - Use the earlier spreadsheet based reporting form for resubmitting reports for 2011 to 2013.

## Background & Rule Changes for 2014



- E-GGRT also reflects changes from the 2014 rule "Addition of GWPs to the General Provisions and Amendments and Confidentiality Determinations for Fluorinated Gas Production" (79 FR 73750, December 11, 2014 and 79 FR 77391, December 24, 2014)
  - Added ~100 chemical-specific GWPs for certain F-GHGs and F-HTFs to Table A-1
  - Added default GWPs for F-GHGs and F-HTF based on the F-GHG group
  - Made conforming changes to subpart I where a default GWP of 2000 was previously defined for certain F-GHGs not in Table A-1

### **Confidential Business Information**



- Confidential data elements in e-GGRT reflect requirements from the 2013 subpart I rule amendments
- Data elements that have been determined to be CBI and those that have no determination must be reported
- Reporting elements that have been determined to be CBI will be protected under the Clean Air Act (Sec. 114(c)) and EPA regulations (40 CFR Part 2)
- Subpart I data elements that are CBI are highlighted in e-GGRT

## Reporting Subpart I Data - Overview

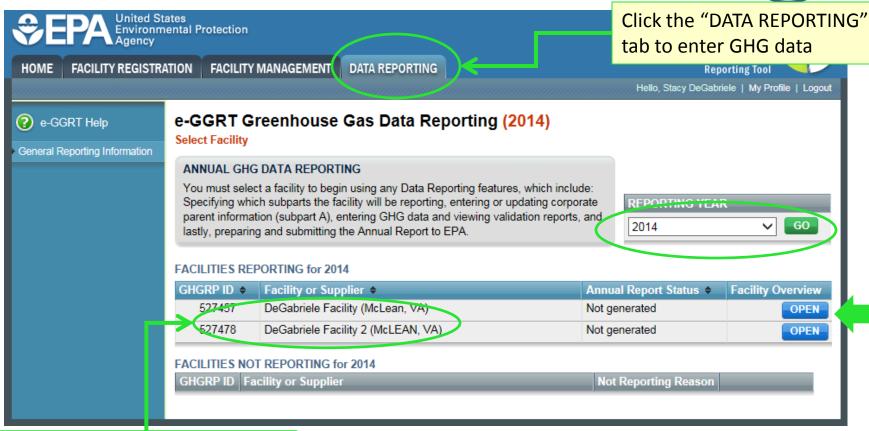


## Reporting of subpart I GHG data:

- Step 1: Accessing the subpart I reporting module to your facility profile in e-GGRT and accessing the Web form.
- Step 2: Enter required facility-specific and fab-specific data into the Web form.
- Step 3: Enter GHG emissions data into the Web form.
- <u>Step 4</u>: Review and correct validation errors.
- Step 5: Generate, certify, and submit annual report.

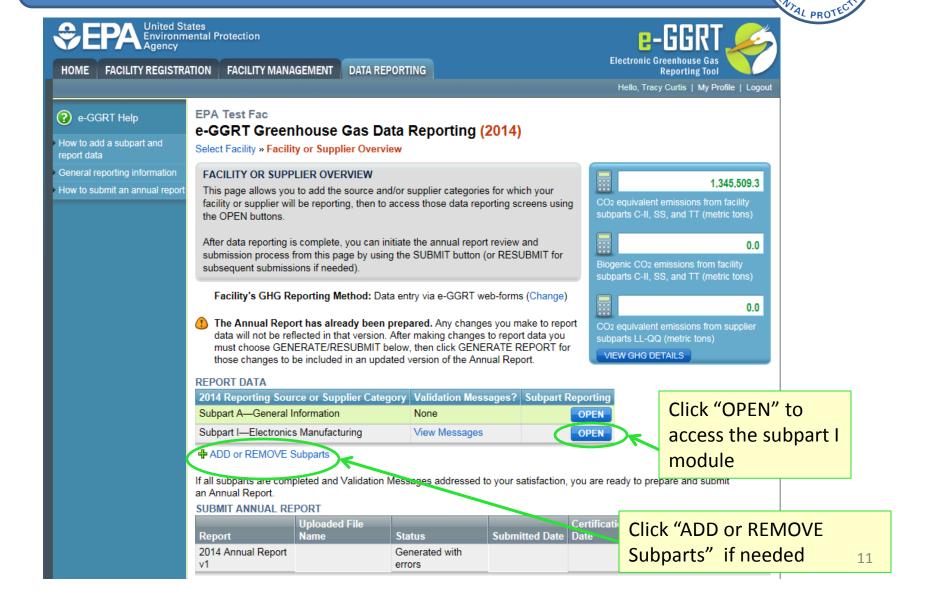
### Step 1: How to Access the Subpart I Module



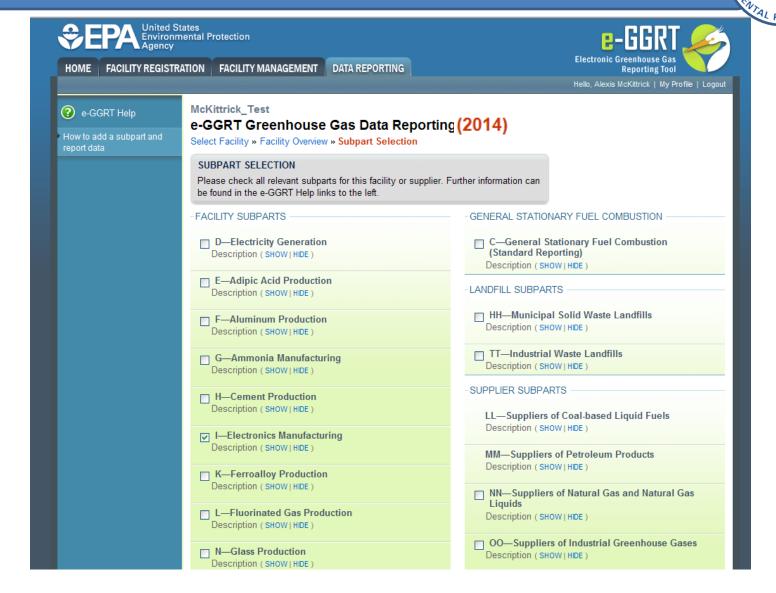


Select the correct facility from your list of REGISTERED FACILITIES

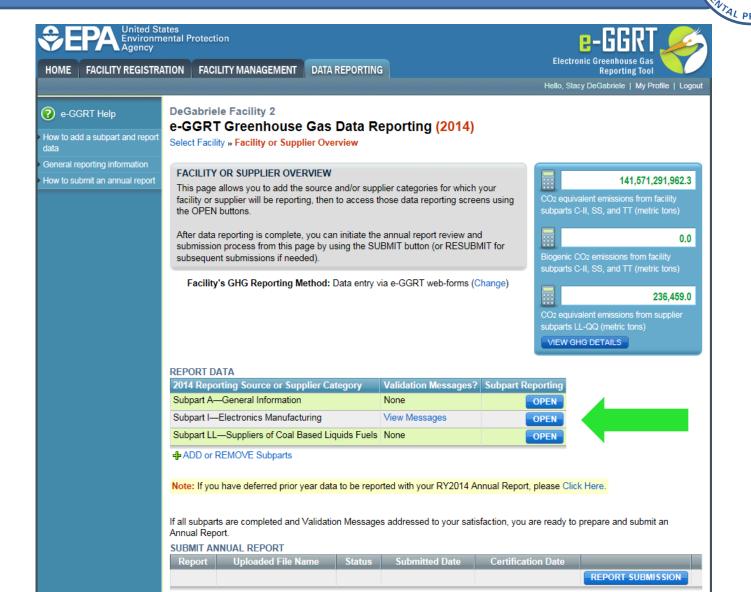
## Step 1: How to Access the Subpart I Module



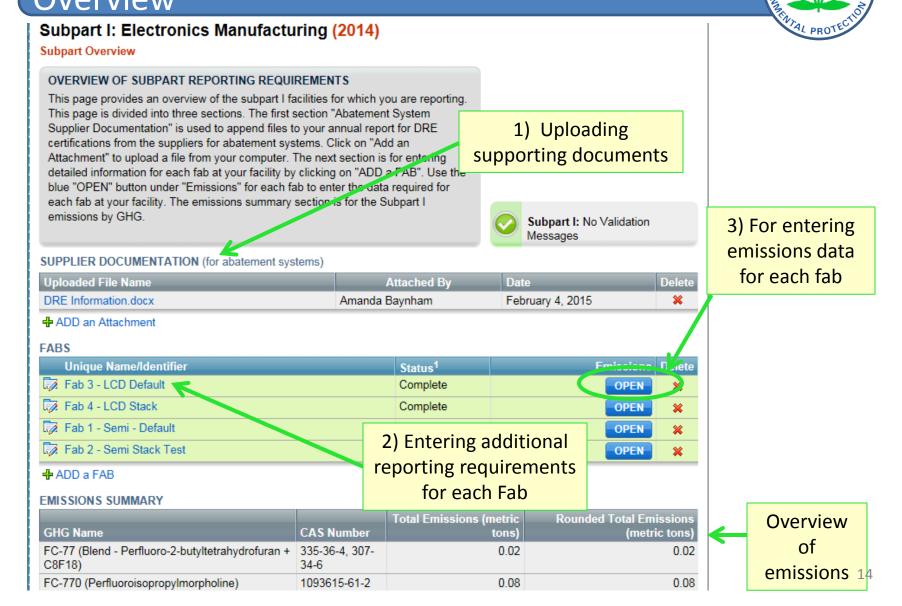
## Step 1: How to Add A Subpart I Module



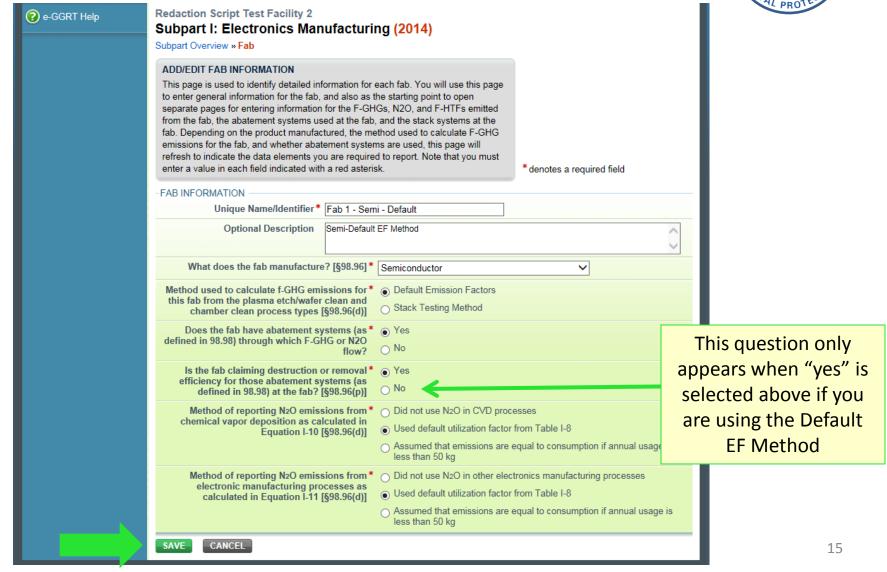
### Step 1: How to Access the Subpart I Module



# Step 2: Completing Subpart I Web Form – Facility



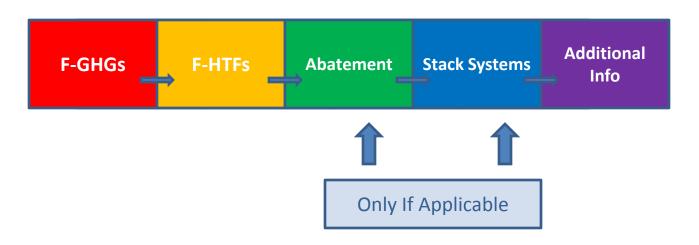
# Step 2: Completing Subpart I Web Form – Adding a Fab



# Step 2: Completing Subpart I Web Form – Entering Fab Information - Overview

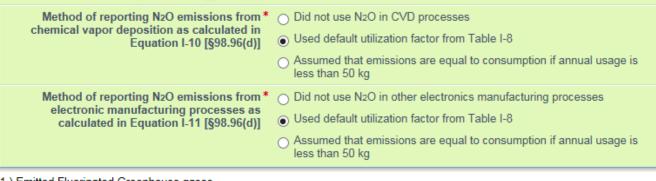


There are five main areas for which you must enter data in the "Fab Information" page.



## Step 2a: Completing Subpart I Web Form – Entering F-GHGs from the Fab

F-GHGs Abatement Stack Systems



#### Emitted Fluorinated Greenhouse gases

In this table, define all F-GHGs that must be reported for this fab. After the fab is completely defined you can use the OPEN button on the Subpart Overview to enter the related emissions information.

F-GHG   CAS No.	Process Type	Delete
No F-GHCs added.  ADD a F-GHG  2.) Fluorinated Heat transfer fluids	Click on "Add a F-GHG"	
In this table, define all F-HTFs that must be reported for this fab. After	the rap is completely defined you cal	n use the OPEN

button on the Subpart Overview to enter the related emissions information.	
F-HTF	Delete
No F-HTFs added.	
♣ ADD or Remove F-HTFs to Report	
3.) Abatement Systems	
The number of abatement systems for each gas and process type combination, and the process types controlled by the abatement systems are considered CBI.	
Abatement System Name/Identifier	Delete
No abatement system added.	
♣ ADD an Abatement System	

## Step 2a: Entering F-GHGs from the Fab (Default EF Method, Semiconductor facilities)



F-GHGs → F-HTFs → Abatement Stack Systems

Subpart I: Electronics Ma	nufacturing (2014)	
Subpart Overview » Fab » F-GHG		
ADD/EDIT F-GHG INFORMATION		
select the F-GHG emitted from the pl process types from the fab. (N2O and "Other F-GHG (specify)" if you are re drop down list (please review the CA	ted from the fab. Use the drop-down list to asma etch/wafer clean and chamber clean if F-HTF are entered on other pages.) Select porting an F-GHG that is not included in the S number and chemical formulas to be sure the Click "SAVE" after entering the information for the tend on a separate page.  * denotes a required field	
FAB INFORMATION		
Unique Name/Identifie	Fab 1 - Semi - Default	
What does the fab manufacture?	Semiconductor	
Method used to calculate f-GHG emissions		
-FLUORINATED GHG EMITTED -		Select a F-GHG from
Flourinated Greenhouse Gas [98.96 (c)(1)]		the drop-down list
Process Type(s) and Calculation Method	od(s)	
In the table below, please select all the to this f-GHG for this fab.	combinations of Process Type and Method of Emissions Calculation that are applicable	
Process Type [98.96(c)(1)]	Method of Emissions Calculation [98.96(d)]	
	Used default factors	
Chamber cleaning - in situ plasma	Assumed utilization/by-product formation rates = 0	Identify all process
	Assumed emissions are equal to consumption if annual usage is less than 50 kg	Identify all process
	Used default factors	types and calculation
Chamber cleaning - remote plasma	Assumed utilization/by-product formation rates = 0	• •
	Assumed emissions are equal to consumption if annual usage is less than 50 kg	methods used for each
Observation in site 4	Used default factors  Assumed utilization/by-product formation rates = 0	gas
Chamber cleaning - in situ thermal	Assumed emissions are equal to consumption if annual usage is less than 50 kg	Pa-2
	Used default factors	
Plasma etching / Wafer cleaning	Assumed utilization/by-product formation rates = 0	
r asma coming r water cleaning	Assumed emissions are equal to consumption if annual usage is less than 50 kg	
SAVE CANCEL FAB 3	Returns to "Fab Information" Page	18

## Step 2a: Entering F-GHGs from the Fab (Default EF Method, LCD/PV/MEMs facilities)



F-GHGs F-HTFs -

Abatement Stack Systems

Process types shown are for LCD/PV/MEMS facilities

Select if your F-GHG is not listed

Suppart I: Electronics I	war	iutacturing (2014)	
Subpart Overview » Fab » F-GHG			
ADD/EDIT F-GHG INFORMATION			
select the F-GHG emitted from the process types from the fab. (N2O "Other F-GHG (specify)" if you are drop down list (please review the	e plas and F repo CAS r st.) Cli	d from the fab. Use the drop-down list to ma etch/wafer clean and chamber clean F-HTF are entered on other pages.) Select riting an F-GHG that is not included in the number and chemical formulas to be sure the ick "SAVE" after entering the information for ered on a separate page.	* denotes a required field
-FAB INFORMATION			
Unique Name/Identi	fier	Fab 3 - LCD Default	
What does the fab manufactu	re?	LCDsMEMsPVs	
Method used to calculate f-G emission		Default Emission Factors	
-FLUORINATED GHG EMITTED -			
Flourinated Greenhouse Gas [98 (c)	3.96 <b>*</b> (1)]	Select HFC-23 (CHF3) , CAS No. 75-46-7	
HFC-32 (CH2F2) , CAS No. 75-10-5 Process Type(s) and Calculation Method( HFC-41 (CH3F) , CAS No. 593-53-3			
In the table below, please select all the co to this f-GHG for this fab.  Sulfur hexafluoride (SF6), CAS No. 2551-62-4 Nitrogen trifluoride (NF3), CAS No. 7783-54-2 PFC-14 (Perfluoromethane) (CF4), CAS No. 75-73-0			
Process Type [98.96(c)(1)]		PFC-116 (Perfluoroethane) (C2F6), CAS No.	. 76-16-4
Chamber cleaning		PFC-218 (Perfluoropropane) (C3F8), CAS No. Perfluorocyclobutane (C-C4F8), CAS No. 11: PFC C-1418 (c-C5F8), CAS No. 559-40-0 Perfluorobuta-1,3-diene (CF2=CFCF=CF2), Octafluorotetrahydrofuran (C4F8O), CAS No. HFC-125 (C2HF5), CAS No. 354-33-6	5-25-3 CAS No. 685-63-2
	L	HEC 134. (CH3ECE3), CAS No. 811-97-2	_
Plasma etching		Other f-GHG (specify)	if appual years is less than 50 kg
		Assumed emissions are equal to consumption  Used default factors	il annual usage is less than 50 kg
NF3 remote chamber cleaning		Assumed utilization/by-product formation rates	s = 0
The orthogonal moor dealing		Assumed emissions are equal to consumption	
SAVE CANCEL FAB			1

## Step 2a: Entering F-GHGs from the Fab (Stack Testing Method, All Facilities)



## Step 2a: Entering Other F-GHGs from the Fab (Default Method, All Facilities)



F-GHGs Abatement Stack Systems

-FLUORINATED GHG EMITTED		
Flourinated Greenhouse Gas [98.96* (c)(1)] Other f-GHG (specify)	~	
- SPECIFY OTHER GHG		
F-GHG Name [98.96(c)(1)]*	Thes	se fields must be
Chemical Formula [98.96(c)(1)]*		oulated for each
Chemical Abstract Registry Number* (CAS No.) [98.96(c)(1)]		r F-GHG" entered.
Group to which this f-GHG belongs*		
F-GHG Group	GWP	
Fully fluorinated GHOs	10000	
Saturated hydrofluorocarbons (HFCs) with 2 or rewell earbon-hydrogen bonds	3700	
Saturated HFCs with 3 or more carbon-hydrogen bonds	930	
Saturated hydrofluoroethers (HFEs) and hydrochlorofluoroethers (HCFEs) with 1 carbon-hydrogen bond	5700	Calaat the area
Saturated HFEs and HCFEs with 2 carbon-hydrogen bonds	2600	Select the app
Saturated HFEs and HCFEs with 3 or more carbon-hydrogen bonds	270	GHG group f
Fluorinated formates	350	GHG ent
Fluorinated acetates, carbonofluoridates, and fluorinated alcohols other than fluorotelomer alcohols	30	CITO CITO
<ul> <li>Unsaturated perfluorocarbons (PFCs), unsaturated HFCs, unsaturated hydrochlorofluorocarbons (HCFCs), unsaturated halogenated ethers, unsaturated halogenated esters, fluorinated aldehydes, and fluorinated ketones</li> </ul>	1	
Fluorotelomer alcohols	1	
Fluorinated GHGs with carbon-iodine bond(s)	1	
Other fluorinated GHGs	2000	
Process Type(s) and Calculation Method(s)		

Select the appropriate F-GHG group for the F-GHG entered.

In the table below, please select all the combinations of Process Type and Method of Emissions Calculation that are applicable to this f-GHG for this fab.

## Step 2a: Entering Other F-GHGs from the Fab (Default Method, All Facilities)

Saturated HEEs and HCEEs with 3 or more earlier hydrogen hands

F-GHGs Abatement Stack Systems SCREEN ERRORS 🔉 You cannot add this greenhouse gas because the CAS Registry Number you have provided for this 'other' gas matches with an existing 40 CFR Part 98 Table A-1 gas, or it matches with an 'other' gas that has already been added. It is possible it is included in the selection list provided, but with a different chemical name than the one you are using. The gas with the matching CAS Registry Number is identified within e-GGRT as follows: CAS Registry Number: 354-33-6; Gas Name: HFC-125; Chemical Formula: C2HF5. If you would like to select this gas, click CANCEL and locate the gas on the selection list provided. If you are unable to locate this gas on the selection list provided, please contact the GHGRP Help Desk FAB INFORMATION Unique Name/Identifier Fab 1 - Semi - Default What does the fab manufacture? Semiconductor Method used to calculate f-GHG **Default Emission Factors** emissions FLUORINATED GHG EMITTED Flourinated Greenhouse Gas [98.96\* Other f-GHG (specify) (c)(1)SPECIFY OTHER GHG **Entering an F-GHG** F-GHG Name [98.96(c)(1)]\* HFC-125 already included in the Chemical Formula [98.96(c)(1)]\* C2HF5 list triggers a screen Chemical Abstract Registry Number \* 354-33-6 (CAS No.) [98.96(c)(1)] error Group to which this f-GHG belongs\* F-GHG Group **GWP**  Fully fluorinated GHGs 10000 Saturated hydrofluorocarbons (HFCs) with 2 or fewer carbon-hydrogen bonds 3700 Saturated HFCs with 3 or more carbon-hydrogen bonds 930 Saturated hydrofluoroethers (HFEs) and hydrochlorofluoroethers (HCFEs) with 1 carbon-hydrogen bond 5700 Saturated HFEs and HCFEs with 2 carbon-hydrogen bonds 2600

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## Step 2a: Entering Other F-GHGs from the Fab (Default Method, All Facilities)



Saturated HFEs and HCFEs with 2 carbon-hydrogen bonds	2600
Saturated HFEs and HCFEs with 3 or more carbon-hydrogen bonds	270
Fluorinated formates	350
Fluorinated acetates, carbonofluoridates, and fluorinated alcohols other than fluorotelomer alcohols	30
<ul> <li>Unsaturated perfluorocarbons (PFCs), unsaturated HFCs, unsaturated hydrochlorofluorocarbons (HCFCs), unsaturated halogenated ethers, unsaturated halogenated esters, fluorinated aldehydes, and fluorinated ketones</li> </ul>	1
Fluorotelomer alcohols	1
Fluorinated GHGs with carbon-iodine bond(s)	1
Other fluorinated GHGs	2000

#### Process Type(s) and Calculation Method(s)

In the table below, please select all the combinations of Process Type and Method of Emissions Calculation that are applicable to this f-GHG for this fab.

Process Type [98.96(c)(1)]	Method of Emissions Calculation [98.96(d)]
	Used default factors
Chamber cleaning - in situ plasma	Assumed utilization/by-product formation rates = 0
	Assumed emissions are equal to consumption if annual usage is less than 50 kg
	Used default factors
Chamber cleaning - remote plasma	Assumed utilization/by-product formation rates = 0
	Assumed emissions are equal to consumption if annual usage is less than 50 kg
	Used default factors
Chamber cleaning - in situ thermal	Assumed utilization/by-product formation rates = 0
	Assumed emissions are equal to consumption if annual usage is less than 50 kg
	Used default factors
Plasma etching / Wafer cleaning	Assumed utilization/by-product formation rates = 0
	Assumed emissions are equal to consumption if annual usage is less than 50 kg
SAVE CANCEL FAB •	

Identify all process types and calculation methods used for the Other F-GHG

## Step 2a: Completing Subpart I Web Form – Entering F-GHGs from the Fab



F-GHGs F-HTFs Abatement Stack Systems Additional Info

1.) Emitted Fluorinated Greenhouse gases				
In this table, define all F-GHGs that must be reported for this fab. After the fab is completely defined you can use the OPEN button on the Subpart Overview to enter the related emissions information.				
F-GHG   CAS No. Proc	cess Type	Delete		
	mber cleaning - in situ plasma,Plasma etching / Wafer cleaning	*		
	ma etching / water cleaning	^		
PFC-116 (Perfluoroethane)   76-16-4 Plast	ma etching / Wafer cleaning	(X)		
♣ ADD a F-GHG		•		
2.) Fluorinated Heat transfer fluids				
In this table, define all F-HTFs that must be reported f button on the Subpart Overview to enter the related en	for this fab. After the fab is completely defined you can use the OPEN missions information.			
F-HTF		Delete		
No F-HTFs added.				
3.) Abatement Systems The number of abatement systems for each gas and pabatement systems are considered CBI.	process type combination, and the process types controlled by the			
Abatement System Name/Identifier		Delete		
No abatement system added.				
ADD an Abatement System				
-ADDITIONAL FAB INFORMATION				
What Is the Diameter of the Wafers Manufactured at this Fab? [§98.96(b)] (select all that apply)	☐ Greater than 300mm ☐ 300mm ☐ 200mm ☐ 150mm ☐ Less than 150mm			
Annual Manufacturing Capacity at this Fab used	CBI (square meters)			

To edit an F-GHG previously entered, click on the chemical name

F-GHGs entered incorrectly may be deleted here.

Click here to add F-HTFs

## Step 2b: Completing Subpart I Web Form – Adding F-HTFs from the Fab (All Facilities)

F-GHGs F-HTFs Abatement Stack Systems

**Additional** 

FLOURINATED HEAT TRANSFER FLUIDS EMITTED AT THE FAB [§98.96(C)(4)]	
☐ HFC-245fa (CHF2CH2CF3) , CAS No. 460-73-1	
☐ HFC-365mfc (CH3CF2CH2CF3) , CAS No. 406-58-6	
☐ HFC-43-10mee (CF3CFHCFHCF2CF3) , CAS No. 138495-42-8	
☐ PFC-4-1-12 (Perfluoropentane) (C5F12) , CAS No. 678-26-2	
☐ PFC-5-1-14 (Perfluorohexane) (C6F14), CAS No. 355-42-0	
☐ PFC-9-1-18 (C10F18) , CAS No. 306-94-5	
☐ HFE-43-10pccc (H-Galden 1040x) (CHF2OCF2OC2F4OCHF2) , CAS No. E1730133	
☐ HFE-134 (CHF2OCHF2) , CAS No. 1691-17-4	
☐ HFE-236ca12 (HG-10) (CHF2OCF2OCHF2) , CAS No. 78522-47-1	
Galden ZT-150 (HCF2OCF2OCF2CF2OCF2H) , CAS No. 161075-02-01 (c)	
☐ HFC-23 (CHF3) , CAS No. 75-46-7	
☐ HFC-125 (C2HF5) , CAS No. 354-33-6	
☐ HFC-134a (CH2FCF3) , CAS No. 811-97-2	Click here to add F
☐ HFC-143a (C2H3F3), CAS No. 420-46-2	HTFs not included
☐ HFC-152a (CH3CHF2) , CAS No. 75-37-6	
☐ Sulfur hexafluoride (SF6) , CAS No. 2551-62-4	the picklist
☐ PFC-116 (Perfluoroethane) (C2F6) , CAS No. 76-16-4	
☐ PFC-5-1-14 (Perfluorohexane) (C6F14), CAS No. 355-42-0	
5 Jon toy Station	







## Step 2b: Completing Subpart I Web Form – Adding F-HTFs from the Fab (All Facilities)



F-GHGs F-HTFs Abatement Stack Systems Additional Info

ADD/EDIT OTHER F-HTF INFORMATION  This page is used to identify "Other F-HTFs" not listed on the "ADD/EDIT F-HTF	
INFORMATION" page. Use the fields below to enter information for each "Other F-HTF" that is not listed in the F-HTF drop-down list. Enter the F-HTF Name, chemical formula, and CAS Number. If the F-HTF is a GHG for which there is not a chemical-specific GWP in Table A-1 of subpart A, select the F-GHG group/GWP to which the F-HTF belongs. Click "SAVE" after entering the information for the "Other F-HTF".  *denotes a required field.	d
SPECIFY OTHER F-HTF	
F-HTF Name [98.96(c)(4)]*	
Chemical Formula [98.96(c)(4)] *	
Chemical Abstract Registry Number * (CAS No.) [98.96(c)(1)]	
Group to which this f-HTF belongs *	
F-GHG Group	GWP
○ Fully fluorinated GHSs	10000
O Saturated hydrofluorocarbons (HFCs) with 2 or news carbon-hydrogen bonds	3700
O Saturated HFCs with 3 or more carbon-hydrogen bonds	930
O Saturated hydrofluoroethers (HFEs) and hydrochlorofluoroethers (HCFEs) with 1 carbon-hydrogen bond	5700
O Saturated HFEs and HCFEs with 2 carbon-hydrogen bonds	2000
O Saturated HFEs and HCFEs with 3 or more carbon-hydrogen bonds	270
Fluorinated formates	
Fluorinated acetates, carbonofluoridates, and fluorinated alcohols other than fluorotelomer alcohols	
<ul> <li>Unsaturated perfluorocarbons (PFCs), unsaturated HFCs, unsaturated hydrochlorofluorocarbons (HCFCs), unsaturated halogenated ethers, unsaturated halogenated esters, fluorinated aldehydes, and fluorinated ketones</li> </ul>	
O Fluorotelomer alcohols	1
Fluorinated GHGs with carbon-iodine bond(s)	1
Other fluorinated GHGs	2000

These fields must be populated for each "Other F-HTF" entered.

Select the appropriate F-GHG group for the F-HTF entered.



Subpart Overview » Fab

## Step 2b: Completing Subpart I Web Form – Adding F-HTFs from the Fab (All Facilities)



F-GHGs F-HTFs Abatement Stack Systems Additional

CFR Part 98 Table A-1 gas, or it matches with an "other" gas that has already been added. It is possible it is it list provided but with a different chemical name than the one you are using. The gas with the CAS Registry Nue-GGRT as follows: CAS Registry Number: 756-13-8; Gas Name: Novec 649/1230, FK 5-1-12, perfluoro(2-mcChemical Formula: C6F12O, If you would like to select this gas, click CANCEL and locate the gas on the selection list provided, please [contact the GHGRP Help Desk].	umber is identified with ethyl-3-pentanone);
PECIFY OTHER F-HTF	
F-HTF Name [98.96(c)(4)] * FK 5-1-12	
Chemical Formula [98.96(c)(4)] * C6F12O	
themical Abstract Registry Number * [756-13-8 (CAS No.) [98.96(c)(1)]	
Group to which this f-HTF belongs *	
F-GHG Group	GWP
Fully fluorinated GHGs	10000
Saturated hydrofluorocarbons (HFCs) with 2 or fewer carbon-hydrogen bonds	370ს
Saturated HFCs with 3 or more carbon-hydrogen bonds	930
Saturated hydrofluoroethers (HFEs) and hydrochlorofluoroethers (HCFEs) with 1 carbon-hydrogen be	ond 5700
Saturated HFEs and HCFEs with 2 carbon-hydrogen bonds	2600
Saturated HFEs and HCFEs with 3 or more carbon-hydrogen bonds	270
Fluorinated formates	350
Fluorinated acetates, carbonofluoridates, and fluorinated alcohols other than fluorotelomer alcohols	30
<ul> <li>Unsaturated perfluorocarbons (PFCs), unsaturated HFCs, unsaturated hydrochlorofluorocarbons (HC unsaturated halogenated ethers, unsaturated halogenated esters, fluorinated aldehydes, and fluorina ketones</li> </ul>	
Fluorotelomer alcohols	1
Fluorinated GHGs with carbon-iodine bond(s)	1
Other fluorinated GHGs	2000

Entering a F-HTF already included in the list triggers a screen error

## Step 2b: Completing Subpart I Web Form – Adding F-HTFs from the Fab (All Facilities)





#### 1.) Emitted Fluorinated Greenhouse gases

In this table, define all F-GHGs that must be reported for this fab. After the fab is completely defined you can use the OPEN button on the Subpart Overview to enter the related emissions information.

F-GHG   CAS No.	Process Type	Delete
PFC-14 (Perfluoromethane)   75-73-0	Chamber cleaning - in situ plasma,Plasma etching / Wafer cleaning	×
PFC-218 (Perfluoropropane)   76-19-7	Plasma etching / Wafer cleaning	×
PFC-116 (Perfluoroethane)   76-16-4	Plasma etching / Wafer cleaning	×

#### ADD a F-GHG

#### 2.) Fluorinated Heat transfer fluids

In this table, define all F-HTFs that must be reported for this fab. After the fab is completely defined you can use the OPEN button on the Subpart Overview to enter the related emissions information.

F-HTF	Delete
FC-77 (Blend - Perfluoro-2-butyltetrahydrofuran + C8F18) (blend)	×
HT-55 (CF3(OCFCF3CF2)n-(OCF2)m-OCF3)	×
HT-90 (CF3(OCFCF3CF2)n-(OCF2)m-OCF3)	×
ADD or Pameria E UTEs to Depart	

#### ADD or Remove F-HTFs to Report

#### 3.) Abatement Systems

The number of abatement systems for each gas and process type combination, and the process types controlled by the abatement systems are considered CBI.

Abatement System Name/Identifier	Delete
No abatement system added.	
ADD an Abatement System	

#### -ADDITIONAL FAB INFORMATION

What Is the Diameter of the Wafers Manufactured at this Fab? [§98.96(b)]	Greater than 300mm
(select all that apply)	300mm
	200mm
	□ 150mm

F-HTFs may be removed here.

Only appears if abatement is claimed at the facility

## Step 2d: Adding Abatement Systems (Default Method, Semiconductor Facilities)



F-GHGs F-HTFs Abatement Stack Systems Additional Info

-FAB INFORMATION						
Unique	Name/Identifier Fa	ab 1 - Semi - Default				
What does the fall	manufacture? Se	emiconductor				
Method used to d	calculate f-GHG De emissions	efault Emission Factors				
-ABATEMENT SYSTE						
Abatement Syst	em Name/Identifier	*  ABATE 1		- Ent	er Unique ID	
screens. Only select the	ss Type/Sub-Type co ose below for which [	ns for this fab mbinations listed below are those that were DRE is being claimed. Use the "Number of a umber of abatement systems controlling en	Abatement Systems" column for each	_		
sub-type or process type For each abatement synumber of abatement s	e, as applicable. stem identifier, the pr ystems controlling en	rocess sub-type or process type being contrinissions for each process sub-type, or process considered CBI.	olled is considered CBI. Additionally, the		Select the F-GHG and person of the second se	nich you are
F-GHG   CAS No.		Process Type/Sub-Type	Number of Abatement ystems		claiming abate	ement
PFC-14 (Perfluoromet	hane)   75-73-0	☐ Chamber cleaning - in situ plasma ☐ Plasma etching / Wafer cleaning	5			
PFC-218 (Perfluoropro	opane)   76-19-7	Plasma etching / Wafer cleaning	2			
PFC-116 (Perfluoroeth	nane)   76-16-4	☐ Plasma etching / Wafer cleaning		_		
For each abatement sy	Type/Sub-Type comb stem identifier, the pr	of for this fab contains listed below. Only select those below cocess sub-type or process type being contrainsions for each process sub-type, or proc	olled is considered CBI. Additionally, the		nter the number of stems controlling e each process type	missions for
		e is considered CBI. CBI	ess type, as applicable, for each gas		1 71	7.
F-GHG   CAS No.	Process Ty	rpe/Sub-Type	Number of Abatement Systems			
N2O   10024-97-2		apor Deposition ronics Manufacturing Processes	2		Click after saving to	enter the
	U Other Ziecti	ones manufacturing 1 10003503			basis for the	DRE 29

## Step 2d: Adding Abatement Systems (Default Method, LCD/PV/MEMs Facilities)



F-GHGS -	F-HTFS Aba	tement Stack Systems	Info
-FAB INFORMATION			- 1
Unique Name/Identifier	Fab 3 - LCD Default		
What does the fab manufacture?	LCDsMEMsPVs		
Method used to calculate f-GHG emissions	Default Emission Factors		
-ABATEMENT SYSTEM INFORMATION Abatement System Name/Identi			
			Select the F-GHG and process
Select f-GHG and Process Type combin	nations for this fab e combinations listed below are those that w	vere entered for this fab on the f.CHC	type/sub-type for which you are
screens. Only select those below for wh	ich DRE is being claimed. Use the "Number fic number of abatement systems controlling	of Abatement Systems" column for each	claiming abatement
For each abatement system identifier, the	ne process sub-type or process type being co	ontrolled is considered CBI. Additionally, the	
number of abatement systems controllin used in the process sub-type or process	g emissions for each process sub-type, or p	rocess type, as applicable, for each gas	Enter the number of abatement
F-GHG   CAS No.	Process Type/Sub-Type	Number of Abatement Systems	systems controlling emissions for
Sulfur hexafluoride   2551-62-4	✓ Plasma etching	3	each process type/sub-type
Nitrogen trifluoride   7783-54-2	✓ NF3 remote chamber cleaning	2	each process type/sub-type
		1	
Select N2O and Process Type combinat		holour for which DDE is being alaimed	Identify if abatement is claimed
" "	combinations listed below. Only select those ne process sub-type or process type being or	ontrolled is considered CBI. Additionally, the	for N2O processes

For each abatement system identifier, the process sub-type or process type being controlled is considered CBI. Additionally, the number of abatement systems controlling emissions for each process sub-type, or process type, as applicable, for each gas used in the process sub-type or process type is considered CBI

F-GHG   CAS No.	Process Type/Sub-Type	Number of Abatement Systems
N2O   10024-97-2	Other Electronics Manufacturing Processes	
SAVE CANCEL	FAB → Basis of DRE→	

## Step 2d: Adding Abatement Systems (Stack Test Method,

All Facilities) F-HTFs Abatement Stack Systems FAB INFORMATION Unique Name/Identifier Fab 4 - LCD Stack What does the fab manufacture? LCDsMEMsPVs Method used to calculate f-GHG Stack Testing Method emissions ABATEMENT SYSTEM INFORMATION Abatement System Name/Identifier \* ABATE 4 For the stack test method, you Select f-GHG and Process Type combinations for this fab must identify the F-GHG and The F-GHG and Process Type/Sub-Type combinations listed below are those that were entered for this fab on the f-GHG screens. Only select those below for which DRE is being claimed. Use the "Number of Abatement Systems" column for each process type for which combination selected to report the specific number of abatement systems controlling emissions of the f-GHG for each process sub-type or process type, as applicable. abatement is claimed For each abatement system identifier, the process sub-type or process type being controlled is considered CBI. Additionally, the number of abatement systems controlling emissions for each process sub-type, or process type as applicable, for each gas used in the process sub-type or process type is considered CBI. F-GHG | CAS No. Process Type/Sub-Type **Number of Abatement Systems** Enter the number of abatement Plasma etching Chamber cleaning Nitrogen trifluoride | 7783-54-2 systems controlling emissions for NF3 remote chamber cleaning each process type/sub-type Plasma etching Chamber cleaning Sulfur hexafluoride I 2551-62-4 NF3 remote chamber cleaning Plasma etching PFC C-1418 | 559-40-0 Chamber cleaning NF3 remote chamber cleaning

Basis of DRE→

## Step 2d: Completing Subpart I Web Form – Entering Basis of DRE (All Facilities)





Process Type/Sub-Type Plasma etching / Wafer cleaning

F-HTFs Abatement Stack Systems

#### Subpart I: Electronics Manufacturing (2014) Subpart Overview » Fab » Abatement System » DRE Information ADD/EDIT DRE INFORMATION This page is used to enter information on the basis of the DRE value used in calculations for each F-GHG and process type combination for which you are claiming DRE on the "Abatement System" screen. If "Default DRE" is selected, you must indicate the supplier documentation that indicates the system is designed to abate F-GHG or N2O. You will also enter the appropriate certifications for the abatement system(s). Click "SAVE" to retain all information entered. \*denotes a required field FAB INFORMATION Unique Name/Identifier Fab 1 - Semi - Default What does the fab manufacture? Semiconductor Method used to calculate f-GHG Default Emission Factors emissions DRE INFORMATION BY GAS AND PROCESS TYPE F-GHG | CAS No. N2O | 10024-97-2 Process Type/Sub-Type Chemical Vapor Deposition Basis of DRE [98.96(q)(2)] Default DRE Site-Specific Measured DRE Supplier documentation that indicates that the system is designed to abate F-If there are no items in the menu, return to the Subpart Overview screen and GHG or N2O, if using the applicable upload the relevant file. Then, return to this screen and you should find the file default DRE for this gas and process combination DRE INFORMATION BY GAS AND PROCESS TYPE F-GHG | CAS No. PFC-14 (Perfluoromethane) | 75-73-0 Process Type/Sub-Type Plasma etching / Wafer cleaning Basis of DRE [98.96(q)(2)] Default DRE Site-Specific Measured DRE DRE INFORMATION BY GAS AND PROCESS TYPE F-GHG | CAS No. PFC-218 (Perfluoropropane) | 76-19-7

The drop down field is used to select the documentation previously uploaded on the "Subpart Overview" page. This field only appears if "Default DRE" is selected.

### Step 2d: Certifying Abatement Systems – (All Facilities)

F-HTFs Abatement Stack Systems



DRE INFORMATION BY GAS AND PROCESS TYPE F-GHG | CAS No. PFC-14 (Perfluoromethane) | 75-73-0 Process Type/Sub-Type Plasma etching / Wafer cleaning Basis of DRE [98.96(q)(2)] Default DRE Site-Specific Measured DRE DRE INFORMATION BY GAS AND PROCESS TYPE F-GHG | CAS No. PFC-218 (Perfluoropropane) | 76-19-7 Process Type/Sub-Type Plasma etching / Wafer cleaning Basis of DRE [98.96(q)(2)] O Default DRE Site-Specific Measured DRE ABATEMENT CERTIFICATIONS Certification that all abatement systems at the facility have been Certified installed, maintained, and operated in accordance with the site O Not Certified maintenance plan for abatement systems that is developed and maintained in your records as specified in 98.97(d)(9). [§98.96(q)] These certifications appear here because you have indicated for one or more of the F-GHG/Process Type combinations selected above that the Basis of DRE is Default DRE. Certified Certification that the site maintenance plan for abatement systems for which emissions are being reported contains manufacturers Not Certified recommendations and specifications for installation, operation, and maintenance for each abatement system. [§98.96(q)] Certification that the abatement systems for which emissions are being Certified reported and for which default DRE are being used were specifically Not Certified designed for fluorinated GHG and N2O abatement, as applicable. [§98.96] CANCEL ■ Abatement System ★ ■

All facilities with abatement must complete this certification

Facilities using the Default DREs in Table I-16 must also complete these certifications.

F-GHGs •

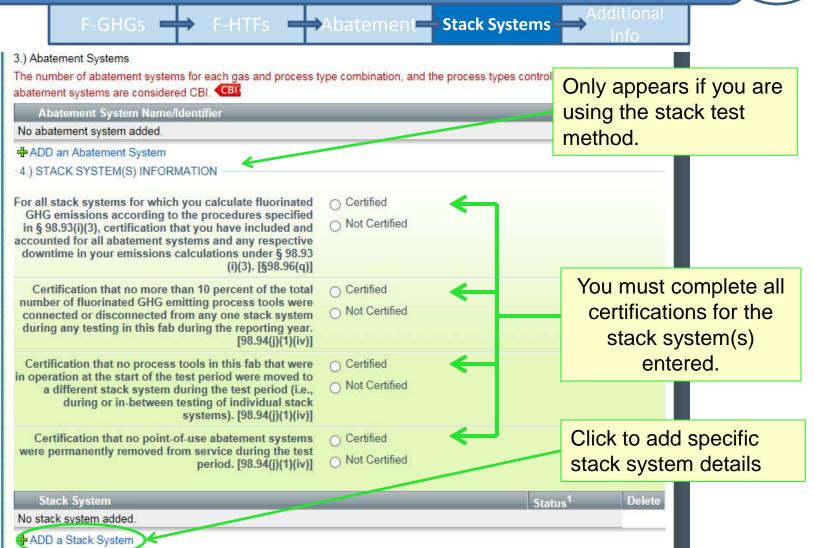
## Step 2d: Certifying Abatement Systems – (All Facilities)



F-GHGs F-HTFs Abatement Stack Systems Info

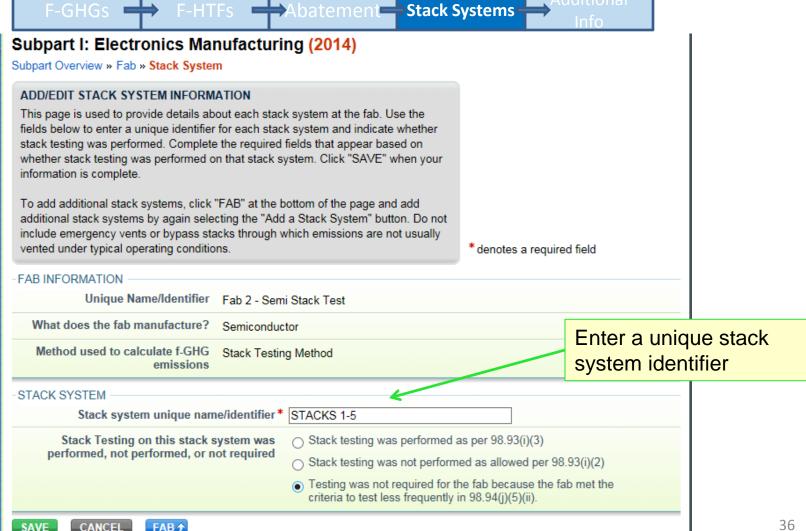
PFC-116 (Perfluoroethane)   76-16-4 Plass	ma etching / Wafer cleaning	×
♣ ADD a F-GHG		
2.) Fluorinated Heat transfer fluids		
In this table, define all F-HTFs that must be reported for button on the Subpart Overview to enter the related er	for this fab. After the fab is completely defined you can use the OPE missions information.	EN
F-HTF	Lists all abotement	Delete
FC-77 (Blend - Perfluoro-2-butyltetrahydrofuran -	+ C8F18) (blend) Lists all abatement	×
HT-55 (CF3(OCFCF3CF2)n-(OCF2)m-OCF3)	system(s) entered	×
HT-90 (CF3(OCFCF3CF2)n-(OCF2)m-OCF3)		×
ADD or Remove F-HTFs to Report		
3.) Abatement Systems		
The number of abatement systems for each gas and	process type combination, and the process types controlled by the	
	process type combination, and the process types controlled by the	
The number of abatement systems for each gas and	process type combination, and the process types controlled by the	Delete
The number of abatement systems for each gas and patternent systems are considered CBI.	process type combination, and the process types controlled by the	Delete
The number of abatement systems for each gas and patternent systems are considered CBI.  Abatement System Name/Identifier	process type combination, and the process types controlled by the	
The number of abatement systems for each gas and pabatement systems are considered CBI.  Abatement System Name/Identifier  ABATE 1	process type combination, and the process types controlled by the	
The number of abatement systems for each gas and pabatement systems are considered CBI.  Abatement System Name/Identifier  ABATE 1	process type combination, and the process types controlled by the	
The number of abatement systems for each gas and pabatement systems are considered CBI.  Abatement System Name/Identifier  ABATE 1  ADD an Abatement System  ADDITIONAL FAB INFORMATION  What Is the Diameter of the Wafers	process type combination, and the process types controlled by the	
The number of abatement systems for each gas and pabatement systems are considered CBI.  Abatement System Name/Identifier  ABATE 1  ADD an Abatement System  ADDITIONAL FAB INFORMATION		

## Step 2e: Entering Stack System Information (Stack Test Method Only)



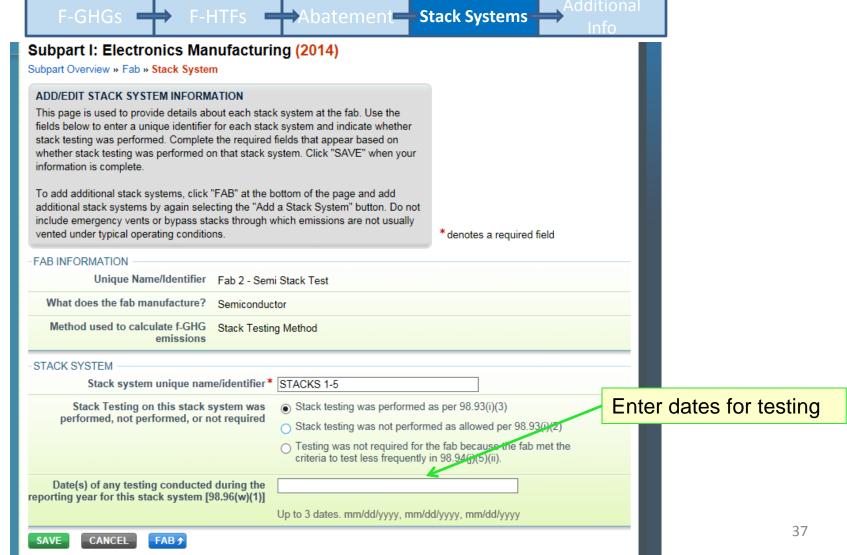
## Step 2e: Entering Stack System Information (Stack Test Method Only)





## Step 2e: Entering Stack System Information (Stack Test Method Only)





## Step 2e: Entering Stack System Information (Stack Test Method Only)

(Optional)

**SAVE** 

CANCEL



F-HTFs Abatement Stack Systems F-GHGs • Subpart I: Electronics Manufacturing (2014) Subpart Overview » Fab » Stack System ADD/FDIT STACK SYSTEM INFORMATION This page is used to provide details about each stack system at the fab. Use the fields below to enter a unique identifier for each stack system and indicate whether stack testing was performed. Complete the required fields that appear based on whether stack testing was performed on that stack system. Click "SAVE" when your information is complete. To add additional stack systems, click "FAB" at the bottom of the page and add additional stack systems by again selecting the "Add a Stack System" button. Do not include emergency vents or bypass stacks through which emissions are not usually vented under typical operating conditions. \*denotes a required field FAB INFORMATION Unique Name/Identifier Fab 2 - Semi Stack Test What does the fab manufacture? Semiconductor Method used to calculate f-GHG Stack Testing Method Appears if stack emissions testing was not STACK SYSTEM Stack system unique name/identifier \* STACKS 1-5 performed Stack Testing on this stack system was Stack testing was performed as per 98.93(i)(3) performed, not performed, or not required Stack testing was not performed as allowed per 98.93(1)(2) Testing was not required for the fab because the fab met the criteria to test less frequently in 98.94(j)(5)(j Indicate why stack testing was not performed.

## Step 2e: Entering Stack System Information (Stack Test Method Only)



F-GHGs F-HTFs Abatement Stack Systems Info

or all stack systems for which you calculate fluorinated	<ul><li>Certified</li></ul>		
GHG emissions according to the procedures specified in § 98.93(i)(3), certification that you have included and counted for all abatement systems and any respective downtime in your emissions calculations under § 98.93 (i)(3). [§98.96(q)]	O Not Certified		
Certification that no more than 10 percent of the total number of fluorinated GHG emitting process tools were connected or disconnected from any one stack system during any testing in this fab during the reporting year. [98.94(j)(1)(iv)]	<ul><li>Certified</li><li>Not Certified</li></ul>		
Certification that no process tools in this fab that were operation at the start of the test period were moved to a different stack system during the test period (i.e., during or in-between testing of individual stack systems). [98.94(j)(1)(iv)]	<ul><li>Certified</li><li>Not Certified</li></ul>		Shows all stack
Certification that no point-of-use abatement systems were permanently removed from service during the test period. [98.94(j)(1)(iv)]	<ul><li>Certified</li><li>Not Certified</li></ul>		systems entered
Stack System		Status <sup>1</sup>	Delete
STACK 6-7		Incomplet	Call Control C
STACKS 1-5		Incomplet	e 💥
₹ STACK 8-10		Incomplet	e 🗱

## Step 2f: Additional Fab Information - Semiconductor Facilities, Default EF or Stack Testing Method



**Additional** 

F-GHGs F-HTFs Abatement Stack Systems Info This question only ADDITIONAL FAB INFORMATION appears for fabs What Is the Diameter of the Wafers Greater than 300mm Manufactured at this Fab? [§98.96(b)] manufacturing □ 300mm (select all that apply) semiconductors. **▼** 200mm 150mm Less than 150mm 1500 CBI (square meters) Annual Manufacturing Capacity at this Fab used in Equation I-5 [§98.96(a)] 1100 CBI (square meters) Annual production for this fab in terms of substrate surface area (e.g., silicon, PV-cell, glass) [§98.96(e)] Yes Do the emissions for this fab include emissions from research and development activities, as O No defined in 98.6? What is the approximate percentage of total Select GHG emissions, on a metric ton CO2e basis, that are attributable to research and development activities? [§98.96(x)] What is the effective fab-wide destruction or (decimal fraction) removal efficiency value calculated using If you do not have abatement, or are using the default method and Equations I-26, I-27 and I-28, as appropriate? are not claiming abatement, enter 0. [**§**98.96(r)]

## Step 2f: Entering Additional Fab Information – All Facilities



**Additional** 

F-HTFs Abatement Stack Systems Info What method was used for this fab to develop Quantifiable metric the apportioning factors for fluorinated GHG and N20 consumption? [§98.96(m)(1)] Optional description of your system and method (s) used in the fab-specific apportioning model Description of quantifiable metric used in wafer passes engineering model to apportion gas consumption [§98.96(m)(1)] Clear Date Start date selected under 98.94(c)(2)(i). [§98.96 12/01/2014 End date selected under 98.94(c)(2)(i). [§98.96 Clear Date 12/31/2014 Certified (based on a single gas corresponding to the largest quantity) Certification that the gas(es) selected under 98.94(c)(2)(ii) for this fab corresponds to the consumed) largest quantity(ies) consumed, on a mass Certified (based on an aggregate of two gases corresponding to the basis, of fluorinated GHG used at the fab in the largest quantities consumed) reporting year which the facility is required to apportion. Note that if you compare the actual gas Not certified consumed to the modeled gas consumed for two fluorinated GHGs, you must certify that one of the fluorinated GHGs selected for comparison corresponds to the largest quantity consumed, on a mass basis, of fluorinated GHGs used at the fab that requires apportionment during the reporting year. [§98.96(m)(3)] Result of calculation comparing actual and (percent) modeled gas consumption under §98.94(c)(2)(v) (the percent difference between actual and modeled gas consumption, relative to actual gas consumption). [§98.96(m)(4)] If you are required to apportion f-GHG Certified (based on a single gas corresponding to the largest quantity) consumption between fabs, as required by 98.94 consumed) (c)(2)(v), certification that the gas(es) you O Certified (based on an aggregate of two gases corresponding to the selected under §98.94(c)(2)(ii) correspond(s) to largest quantities consumed) the largest quantities consumed on a mass basis, of f-GHG used at your facility during the Not certified reporting year for which you are required to apportion. [§98.96(m)(5)]

SAVE

## Reporting Subpart I Data - Overview



## Reporting of subpart I GHG data:



Step 1: Accessing the subpart I reporting module to your facility profile in e-GGRT and accessing the Web form.



<u>Step 2</u>: Enter required facility-specific and fab-specific data into the Web form.



Step 3: Enter GHG emissions data into the Web form.

- Step 4: Review and correct validation errors.
- Step 5: Generate, certify, and submit annual report.

# Step 3: Completing Subpart I Web Form – Entering Emissions for Each Fab

#### Subpart I: Electronics Manufacturing (2014)

#### **Subpart Overview**

#### OVERVIEW OF SUBPART REPORTING REQUIREMENTS

This page provides an overview of the subpart I facilities for which you are reporting. This page is divided into three sections. The first section "Abatement System Supplier Documentation" is used to append files to your annual report for DRE certifications from the suppliers for abatement systems. Click on "Add an Attachment" to upload a file from your computer. The next section is for entering detailed information for each fab at your facility by clicking on "ADD a FAB". Use the blue "OPEN" button under "Emissions" for each fab to enter the data required for each fab at your facility. The emissions summary section is for the Subpart I emissions by GHG.



#### SUPPLIER DOCUMENTATION (for abatement systems)

Uploaded File Name	Attached By	Date	Delete
DRE Information.docx	Amanda Baynham	February 4, 2015	×

#### ADD an Attachment

#### **FABS**

Unique Name/Identifier	Status <sup>1</sup>	Emissions	Delete
Fab 3 - LCD Default	Complete	OPEN	×
Fab 4 - LCD Stack	Complete	OPEN	×
Fab 1 - Semi - Default	Incomplete	OPEN	<b>) *</b>
Fab 2 - Semi Stack Test	Complete	OPEN	×

#### ADD a FAB

#### **EMISSIONS SUMMARY**

GHG Name	CAS Number	Total Emissions (metric tons)	
FC-77 (Blend - Perfluoro-2-butyltetrahydrofuran + C8F18)		0.02	0.02

## Step 3a: Entering Emissions for Each Fab – N<sub>2</sub>O Emissions



### Subpart I: Electronics Manufacturing (2014)

Subpart Overview » Fab

#### ADD/EDIT FAB N20 EMISSIONS INFORMATION

This page is used to enter information about N2O emissions at the fab. Using the fields below, indicate the emissions of N2O for each process type.

\*denotes a required field

#### FAB INFORMATION

Unique Name/Identifier Fab 3 - LCD Default

What does the fab manufacture? LCDsMEMsPVs

Method used to calculate f-GHG Default Emission Factors

If you previously indicated that you did not use N2O in CVD processes, this will be reflected on the emissions page.

#### FOR CHEMICAL VAPOR DEPOSITION PROCESSES IN THIS FAB

Chosen method of reporting N2O emissions from chemical vapor deposition as calculated in Equation I10 [§98.96(d)]

Did not use N2O in CVD processes

#### FOR OTHER ELECTRONICS MANUFACTURING PROCESSES IN THIS FAB

Chosen method of reporting N2O Used default utilization factor from Table I-8 emissions from electronic manufacturing processes as calculated in Equation I-11 [§98.96(d)]

Total annual N2O emissions from electronic manufacturing processes as calculated in Equation I-11 [§98.96(c)(3)] (metric tons)

After saving, click to proceed to next page.

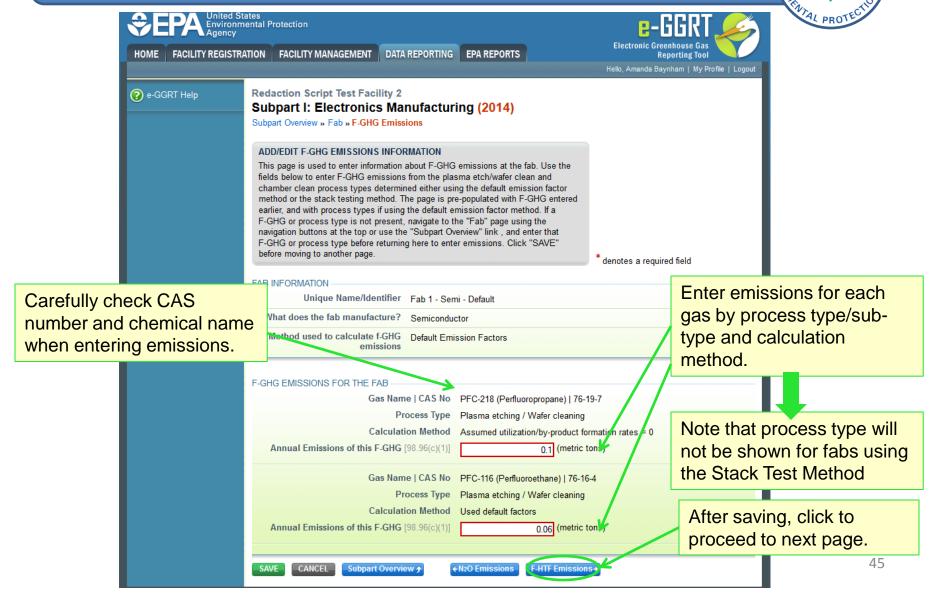
SAVE

CANCEL

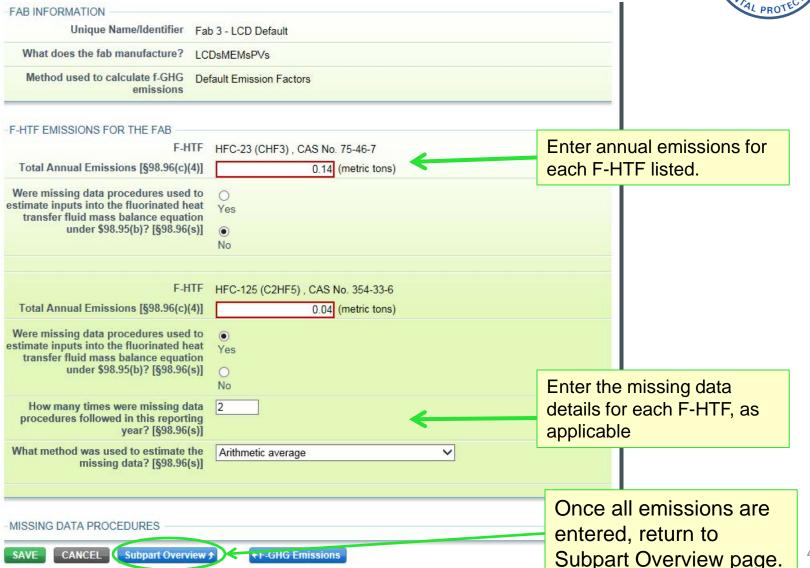
Subpart Overview 1

F-GHG Emissions >

## Step 3b: Entering Emissions for Each Fab — F-GHG Emissions



## Step 3c: Entering Emissions for Each Fab – F-HTF Emissions



### Step 4: Data Validation Checks



### Subpart I: Electronics Manufacturing (2014)

**Subpart Overview** 

#### OVERVIEW OF SUBPART REPORTING REQUIREMENTS

This page provides an overview of the subpart I facilities for which you are reporting. This page is divided into three sections. The first section "Abatement System Supplier Documentation" is used to append files to your annual report for DRE certifications from the suppliers for abatement systems. Click on "Add an Attachment" to upload a file from your computer. The next section is for entering detailed information for each fab at your facility by clicking on "ADD a FAB". Use the blue "OPEN" button under "Emissions" for each fab to enter the data required for each fab at your facility. The emissions summary section is for the Subpart I emissions by GHG.



#### SUPPLIER DOCUMENTATION (for abatement systems)

Uploaded File Name	Attached By	Date	Delete
DRE Information.docx	Amanda Baynham	February 4, 2015	×

#### ADD an Attachment

#### **FABS**

Unique Name/Identifier	Status <sup>1</sup>	Emissions Delete
Fab 3 - LCD Default	Complete	OPEN 💥
Fab 4 - LCD Stack	Complete	OPEN X
Fab 1 - Semi - Default	Incomplete	OPEN X
Fab 2 - Semi Stack Test	Complete	OPEN 💥

#### ADD a FAB

#### **EMISSIONS SUMMARY**

EWISSIONS SUMMANT							
		Total Emissions (metric	Rounded Total Emissions				
GHG Name	CAS Number	tons)	(metric tons)				
FC-77 (Blend - Perfluoro-2-butyltetrahydrofuran +	335-36-4,	0.02	0.02				
C8F18)	307-34-6						

### Step 4: Data Validation Checks



#### Subpart I: Electronics Manufacturing (2014)

Subpart Overview » Validation Report

#### SUBPART VALIDATION REPORT

This report contains a complete set of validation messages at the subpart level. Clicking the message text will redirect you to the screen that contains the field that generated the validation message.



#### FACILITY-LEVEL VALIDATION MESSAGES

Validation Type<sup>1</sup> ID<sup>2</sup> Message<sup>3</sup>
No facility-level validation messages found.

#### FILE-LEVEL VALIDATION MESSAGES

Validation Type <sup>1</sup>	ID <sup>2</sup>	Details	Message <sup>3</sup>
No file-level validation messages found.			

#### **FAB VALIDATION MESSAGES**

Validation Type <sup>1</sup>	Fab	Gas	Process Type	ID <sup>2</sup>	Message <sup>3</sup>
Data Completeness	Fab 1 - Semi - Default	PFC-14 (Perfluoromethane)	Chamber cleaning - in situ plasma	10201	Annual emissions for this fluorinated greenhouse gas. This data element is required.
Data Completeness	Fab 1 - Semi - Default	PFC-14 (Perfluoromethane)	Plasma etching / Wafer	10201	Annual emissions for this fluorinated greenhouse gas. This data element is required.

#### Subpart Overview

- <sup>1</sup> Validation or Verification Types: e-GGRT generates a variety of validation or verification types, defined below:
  - · Data Completeness: data required for reporting is missing or incomplete.
- Data Quality: data is outside of the range of expected values. The value you have provided is outside the EPA
  estimated range for this data element. Please double check this value and revise, if necessary. If you believe it to
  be correct, please submit the value as is.
- Screen Error: a data value or combination of data values prevents e-GGRT from continuing to the next page.
   Typically, this will not appear on the Validation Report, but instead will be displayed on the data entry page at the time the error was created.

<sup>2</sup> ID: Each validation or verification message has a unique identifier. If you contact the e-GGRT Help Desk with a question about a validation message, please include this unique identifier with your request.

Click on a validation message to open the appropriate page of the webform.

<sup>3</sup> The absence of a validation or verification message does not indicate that the information provided is without error.

## Step 5: Generate, certify, and submit annual report



#### e-GGRT Greenhouse Gas Data Reporting (2014)

Select Facility » Facility or Supplier Overview

#### **FACILITY OR SUPPLIER OVERVIEW**

This page allows you to add the source and/or supplier categories for which your facility or supplier will be reporting, then to access those data reporting screens using the OPEN buttons.

After data reporting is complete, you can initiate the annual report review and submission process from this page by using the SUBMIT button (or RESUBMIT for subsequent submissions if needed).

Facility's GHG Reporting Method: Data entry via e-GGRT web-forms (Change)

The Annual Report has already been prepared. Any changes you make to report data will not be reflected in that version. After making changes to report data you must choose GENERATE/RESUBMIT below, then click GENERATE REPORT for those changes to be included in an updated version of the Annual Report.



#### REPORT DATA

 2014 Reporting Source or Supplier Category
 Validation Messages?
 Subpart Reporting

 Subpart A—General Information
 None
 OPEN

 Subpart I—Electronics Manufacturing
 None
 OPEN

ADD or REMOVE Subparts

Note: If you have deferred prior year data to be reported with your RY2014 Annual Report, please Click Here.

If all subparts are completed and Validation Messages addressed to your satisfaction, you are ready to prepare and submit an Annual Report.

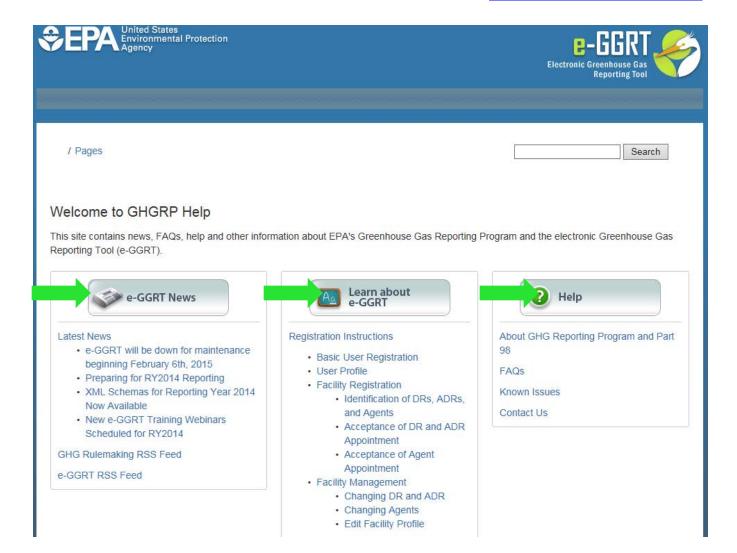
#### SUBMIT ANNUAL REPORT

OUDINITY THINTONIE THE	0111					
Report	Uploaded File Name	Status	Submitted Date	Certification Date		
2014 Annual Report v1		Ready for review			REPORT SUBMISSION	×

Enter data for all applicable subparts before generating the report.

### Help with E-GGRT

Additional information on e-GGRT can be found at www.ccdsupport.com

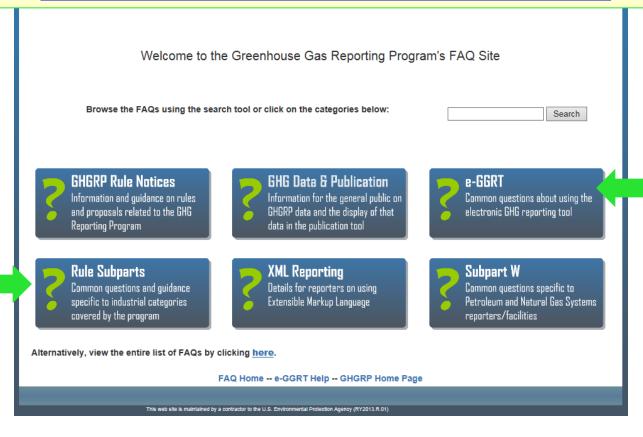


### Answers to Frequently Asked Questions





Answers to common questions can be found on our FAQ site: <a href="http://www.ccdsupport.com/confluence/display/faq/FAQs">http://www.ccdsupport.com/confluence/display/faq/FAQs</a>



### E-GGRT Help Desk







/ Pages / Home / Contact Us

Search

#### **GHGRP Help Desk Contact Information**

The GHGRP Help Desk provides answers to questions about e-GGRT and, more broadly, about the Greenhouse Gas Reporting Program (GHGRP). You may contact the GHGRP Help Desk by email, web, or telephone:

① As a reminder, please do not submit sensitive or business confidential information to the helpline. Anything you send to this address may be made available to the public.

Email	GHGreporting@epa.gov
Web	Submit a question about e-GGRT or the GHGRP
Telephone	1-877-444-1188 (toll free) 1-703-676-4400 (outside U.S.)
Mailing Address	GHGRP Help Desk Mailing Address

The GHGRP Help Desk is open from 9 a.m. to 5 p.m. Eastern Time, Monday through Friday except holidays.

e-GGRT -- Help -- FAQ -- GHGRP

### Help with Subpart I



- GHG Reporting Rule Information and Help <a href="http://www.epa.gov/ghgreporting/reporters/index.html">http://www.epa.gov/ghgreporting/reporters/index.html</a>
- Subpart I Information:
   <a href="http://www.epa.gov/ghgreporting/reporters/subpart/i.html">http://www.epa.gov/ghgreporting/reporters/subpart/i.html</a>
- Register for upcoming webinars on general GHGRP updates and find copies of the slides for this and other webinars:
   <a href="http://www.epa.gov/ghgreporting/reporters/training/index.html">http://www.epa.gov/ghgreporting/reporters/training/index.html</a>

### Questions?



### e-GGRT Help Desk Contact Information

**Email:** <u>GHGreporting@epa.gov</u>

**Telephone:** 1-877-444-1188 (toll free)

1-703-676-4400 (outside U.S.)

### Submit an online form here:

http://www.epa.gov/ghgreporting/contactus.html